

Supporting Information for

Towards High Capacitive Performance of Chemically Deposited β -Ni(OH)₂ Nanolamellae Electrode Films

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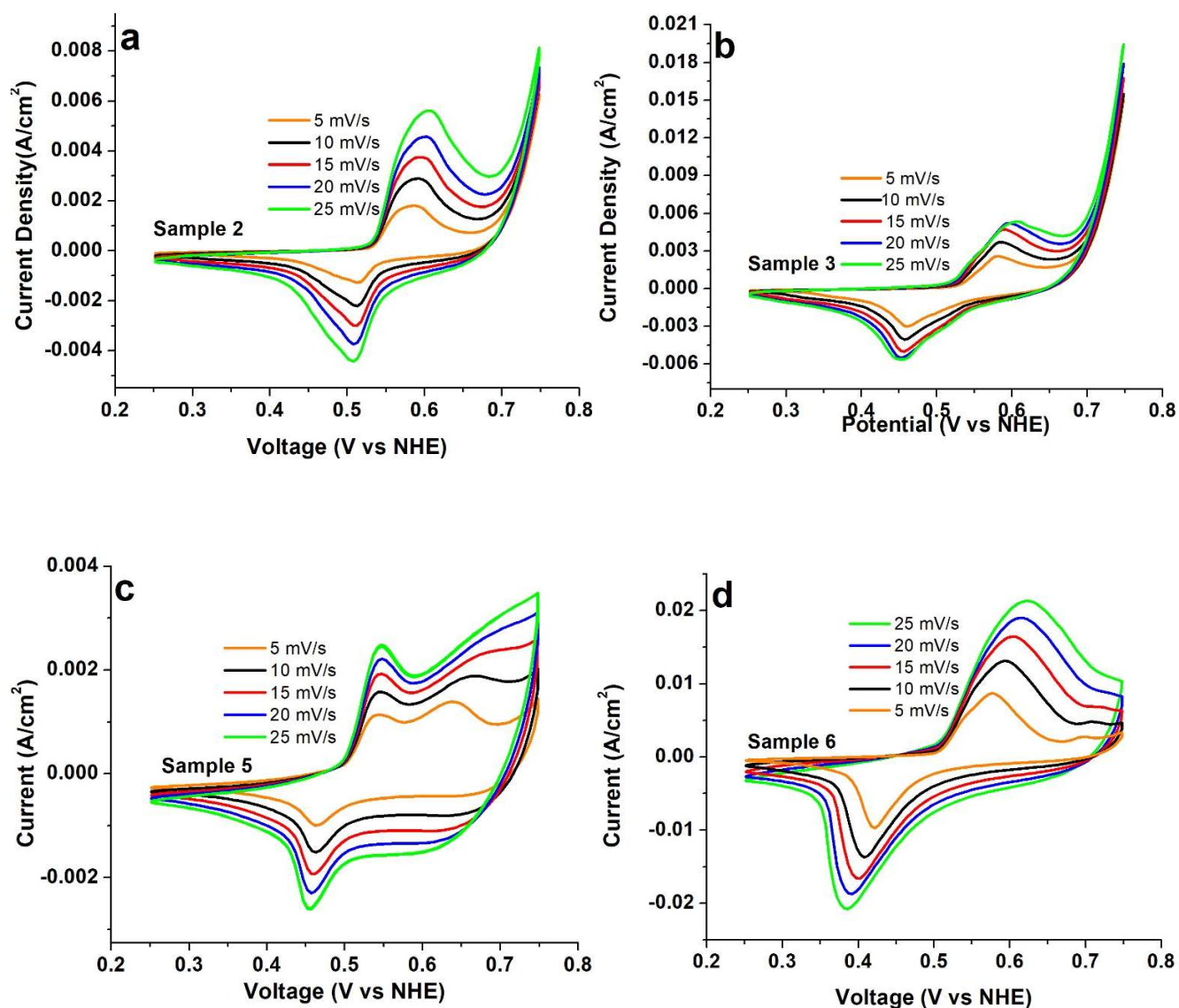


Figure S1. CV curves collected at different scan rates for (a) sample 2 made with lower ammonia content, (b) sample 3 made only in the presence of nickel chloride hexahydrate and ammonia, (c) sample 5 made with lower ammonia content similar to sample 2 but on a textured substrate and (d) sample 6 made only in the presence of nickel chloride hexahydrate and ammonia similar to sample 3 but on a textured substrate. The double peaks observed at lower scan rates in (c) is due to incomplete conditioning of the hierarchical structure at 25 mVs^{-1} .

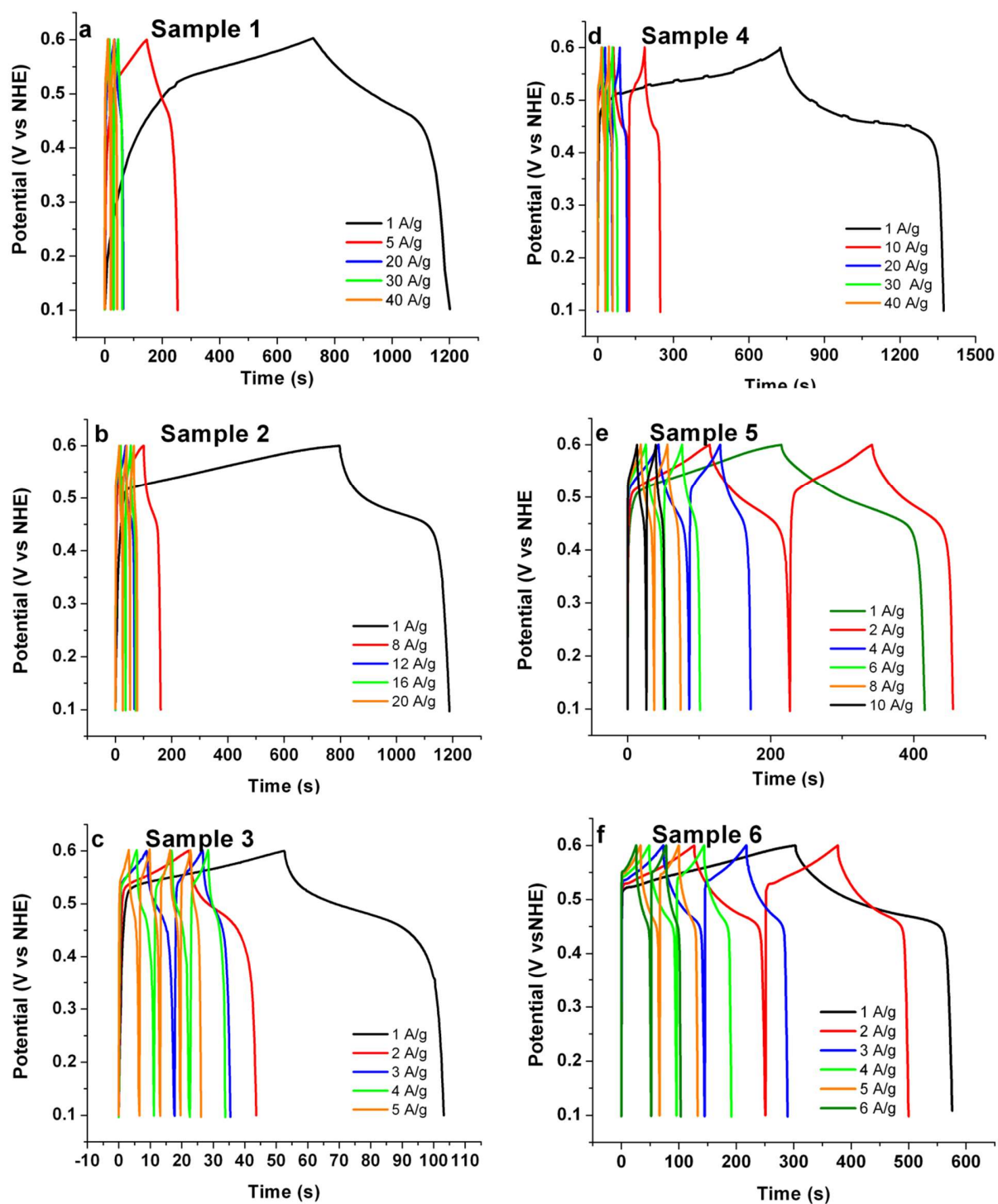


Figure S2. Charge/Discharge curves collected at different current density for (a) standard procedure β -Ni(OH)₂ sample 1, (b) sample 2 made with lower ammonia content, (c) sample 3 made only in the presence of nickel chloride hexahydrate and ammonia, (d) sample 4 made with similar standard procedure as sample 1 but on a textured substrate, (e) sample 5 made with lower ammonia content similar to sample 2 but on a textured substrate and (f) sample 6 made only in

the presence of nickel chloride hexahydrate and ammonia similar to sample 3 but on a textured substrate.